

ASMMC.006AUS



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Raaijmakers et al.
App. No. : 09/452,844
Filed : December 3, 1999
For : CONFORMAL THIN FILMS OVER
TEXTURED CAPACITOR ELECTRODES
Examiner : R. Rocchegiani
Group Art Unit : 2825

INFORMATION DISCLOSURE STATEMENT

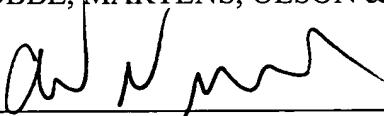
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed is form PTO-1449 listing 5 references that are also enclosed. This Information Disclosure Statement is being filed concurrently with a Request for Continued Examination under 37 C.F.R. § 1.114 and no fee is believed due. The Commissioner is hereby authorized to charge any additional fees which may be required or to credit any overpayment to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

By: 

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Dated: August 14, 2003

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| FORM PTO-1449 <i>102</i> O AUG 18 2003 PATENT & TRADEMARK OFFICE | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY) | ATTY. DOCKET NO. ASMMC.006AUS | APPLICATION NO. 09/452,844 |
| | | APPLICANT Raaijmakers et al. | |
| | | FILING DATE December 3, 1999 | GROUP 2825 |

| U.S. PATENT DOCUMENTS | | | | | | |
|-----------------------|-----------------|----------|-------------|-------|----------|------------------------------|
| EXAMINER INITIAL | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | FILING DATE (IF APPROPRIATE) |
| 1 | 6,270,572 | 08/07/01 | Kim et al. | | | |
| 2 | 6,335,240 | 01/01/02 | Kim et al. | | | |
| 3 | 5,923,056 | 07/13/99 | Lee et al. | | | |
| 4 | 6,342,712 | 01/29/02 | Miki et al. | | | |

| EXAMINER INITIAL | OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.) |
|------------------|---|
| 5 | Materro et al., "Effect of water dose on the atomic layer deposition rate of oxide thin films." Thin Solid Films 368 (2000), pgs. 1-7 |

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|--|-----------------|
| EXAMINER | DATE CONSIDERED |
| *EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT. | |